

	Type	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s
1	BRS	98	(cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/07 16:22		0
2	BRS	47	(cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$31 and @pd<=20001130	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/07 16:26		0
3	BRS	0	((cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$31 and @pd<=20001130) not ((cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/07 16:27		0
4	BRS	51	((cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$3) not ((cetyltrimethylammonium adj (bromide or chloride or Br or Cl or fluoride or F or halide)) and polish\$31 and @pd<=20001130)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/02/07 16:30		0

	Type	L #	Hits	Search Text	DBs	Time Stamp	C o m m e n t s	E r r o r s	E r r o r s
1	BRS	L1	10	(cmp or "chemical mechanical polishing") and (("citric acid salt" or "potassium citrate") same ("H.sub.2 O.sub.2" or peroxide or "hydrogen peroxide"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/02 17:58			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Com men ts	Er ro r D ef in iti on	Er ro rs
1	BRS	L1	51	((typical or conventional) with (slurry) with (pH)) same (cmp or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 11:58			0
2	BRS	L8	21	(MW or "molecular weight") with ("potassium citrate")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 12:18			0
3	BRS	L15	3616	(commercial\$2 with (peroxide or "H=sub.2 O.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 12:22			0
4	BRS	L22	71	15 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 12:38			0
5	BRS	L29	110	("precipitated" adj2 (abrasive or (silica or ("SiO.sub.2")))) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 12:38			0
6	BRS	L36	36	29 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/03 12:38			0